

David Cameron

List of Publications by Citations

Source: <https://exaly.com/author-pdf/6646206/david-cameron-publications-by-citations.pdf>

Version: 2024-04-27

This document has been generated based on the publications and citations recorded by exaly.com. For the latest version of this publication list, visit the link given above.

The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

129
papers

3,810
citations

31
h-index

57
g-index

138
ext. papers

4,058
ext. citations

3.4
avg, IF

5.21
L-index

#	Paper	IF	Citations
129	Aluminum-doped zinc oxide transparent conductors deposited by the sol-gel process. <i>Thin Solid Films</i> , 1994 , 238, 83-87	2.2	316
128	Spatial atomic layer deposition: A route towards further industrialization of atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 010802	2.9	248
127	Optical and electrical properties of transparent conductive ITO thin films deposited by sol-gel process. <i>Thin Solid Films</i> , 2000 , 377-378, 455-459	2.2	241
126	MBE-grown fluoride films: A new class of epitaxial dielectrics. <i>Journal of Vacuum Science and Technology</i> , 1981 , 19, 415-420		165
125	Vibrational properties of carbon nitride films by Raman spectroscopy. <i>Thin Solid Films</i> , 1998 , 332, 62-68	2.2	137
124	Preparation and properties of transparent conductive aluminum-doped zinc oxide thin films by sol-gel process. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001 , 19, 1642-1646	2.9	137
123	Investigation of annealing effects on sol-gel deposited indium tin oxide thin films in different atmospheres. <i>Thin Solid Films</i> , 2002 , 420-421, 76-82	2.2	133
122	Electroluminescent zinc sulphide devices produced by sol-gel processing. <i>Thin Solid Films</i> , 1996 , 280, 221-226	2.2	122
121	Preparation and Characterization of TiO ₂ Thin Films by Sol-Gel Method. <i>Journal of Sol-Gel Science and Technology</i> , 2002 , 25, 137-145	2.3	113
120	Characterization of transparent conductive ITO thin films deposited on titanium dioxide film by a sol-gel process. <i>Surface and Coatings Technology</i> , 2001 , 142-144, 776-780	4.4	65
119	Titanium dioxide thin films, their structure and its effect on their photoactivity and photocatalytic properties. <i>Thin Solid Films</i> , 2009 , 517, 6666-6670	2.2	61
118	Effect of surface treatment on the adhesion of DLC film on 316L stainless steel. <i>Surface and Coatings Technology</i> , 2003 , 163-164, 541-545	4.4	57
117	Review Article: Recommended reading list of early publications on atomic layer deposition Outcome of the Virtual Project on the History of ALD <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 010801	2.9	55
116	An atomic layer deposition process for moving flexible substrates. <i>Chemical Engineering Journal</i> , 2011 , 171, 345-349	14.7	54
115	Atomic layer deposition on polymer based flexible packaging materials: Growth characteristics and diffusion barrier properties. <i>Thin Solid Films</i> , 2011 , 519, 3146-3154	2.2	54
114	Bonding structure in carbon nitride films: variation with nitrogen content and annealing temperature. <i>Surface and Coatings Technology</i> , 1999 , 112, 133-139	4.4	52
113	White paper on the future of plasma science and technology in plastics and textiles. <i>Plasma Processes and Polymers</i> , 2019 , 16, 1700228	3.4	51

112	The characteristics of thin film electroluminescent displays produced using sol-gel produced tantalum pentoxide and zinc sulfide. <i>Thin Solid Films</i> , 2004 , 447-448, 85-89	2.2	49
111	Roll-to-roll atomic layer deposition process for flexible electronics encapsulation applications. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014 , 32, 051603	2.9	46
110	Adhesion of Ti and TiC Coatings on PMMA Subject to Plasma Treatment: Effect of Intermediate Layers of Al ₂ O ₃ and TiO ₂ Deposited by Atomic Layer Deposition. <i>Plasma Processes and Polymers</i> , 2009 , 6, 631-641	3.4	46
109	Atomic layer deposited TiO ₂ films in photodegradation of aqueous salicylic acid. <i>Separation and Purification Technology</i> , 2009 , 66, 130-134	8.3	44
108	Plasma-Assisted Atomic Layer Deposition of Al ₂ O ₃ at Room Temperature. <i>Plasma Processes and Polymers</i> , 2009 , 6, S237-S241	3.4	44
107	Performance of RC and PES ultrafiltration membranes in filtration of pulp mill process waters. <i>Desalination</i> , 2010 , 264, 249-255	10.3	41
106	Comparison of direct and indirect plasma oxidation of NO combined with oxidation by catalyst. <i>Fuel</i> , 2015 , 144, 137-144	7.1	39
105	Utilisation of continuous atomic layer deposition process for barrier enhancement of extrusion-coated paper. <i>Surface and Coatings Technology</i> , 2011 , 205, 3916-3922	4.4	38
104	PECVD of biocompatible coatings on 316L stainless steel. <i>Surface and Coatings Technology</i> , 2005 , 200, 1031-1035	4.4	37
103	Magnetron sputtering of tin protective coatings for medical applications. <i>Journal of Materials Processing Technology</i> , 1996 , 56, 422-430	5.3	35
102	Molecular layer deposition of polyethylene terephthalate thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A121	2.9	34
101	Zinc sulfide thin films produced by sulfidation of sol-gel deposited zinc oxide. <i>Thin Solid Films</i> , 2001 , 398-399, 24-28	2.2	34
100	Electrical properties of reactively sputtered CN _x films. <i>Thin Solid Films</i> , 1999 , 341, 94-100	2.2	34
99	Growth of CuCl thin films by magnetron sputtering for ultraviolet optoelectronic applications. <i>Journal of Applied Physics</i> , 2006 , 100, 033520	2.5	33
98	Surface modification of acetaminophen particles by atomic layer deposition. <i>International Journal of Pharmaceutics</i> , 2017 , 525, 160-174	6.5	31
97	Comparison of ALD coated nanofiltration membranes to unmodified commercial membranes in mine wastewater treatment. <i>Separation and Purification Technology</i> , 2018 , 192, 69-77	8.3	31
96	Optical and electronic properties of carbon nitride. <i>Surface and Coatings Technology</i> , 2003 , 169-170, 245-250	4.4	31
95	Low temperature temporal and spatial atomic layer deposition of TiO ₂ films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 041512	2.9	30

94	Structural variations in CrN/NbN superlattices. <i>Surface and Coatings Technology</i> , 2001 , 142-144, 567-572	4.4	30
93	Evidence for continuous areas of crystalline β -Si ₃ N ₄ in sputter-deposited thin films. <i>Journal of Materials Research</i> , 1999 , 14, 2359-2363	2.5	30
92	Room-temperature ultraviolet luminescence from β -CuCl grown on near lattice-matched silicon. <i>Journal of Applied Physics</i> , 2005 , 98, 1135-12	2.5	28
91	Magnetron-sputtered carbon nitride (CN _x) films. <i>Surface and Coatings Technology</i> , 1995 , 74-75, 696-703	4.4	28
90	Plasma deposition of cubic boron nitride films from non-toxic material at low temperatures. <i>Surface and Coatings Technology</i> , 1991 , 49, 416-421	4.4	28
89	Stress and adhesion in DLC coatings on 316L stainless steel deposited by a neutral beam source. <i>Journal of Materials Processing Technology</i> , 2003 , 141, 127-131	5.3	27
88	Zinc release from atomic layer deposited zinc oxide thin films and its antibacterial effect on Escherichia coli. <i>Applied Surface Science</i> , 2013 , 287, 375-380	6.7	26
87	Chemical and microstructural modifications in LiPON thin films exposed to atmospheric humidity. <i>Solid State Ionics</i> , 2011 , 185, 47-51	3.3	26
86	The deposition of insulators onto InP using plasma-enhanced chemical vapour deposition. <i>Thin Solid Films</i> , 1981 , 85, 61-69	2.2	26
85	InP metal/oxide/semiconductor devices incorporating Al ₂ O ₃ dielectrics chemically vapour deposited at low pressure. <i>Thin Solid Films</i> , 1982 , 91, 339-348	2.2	26
84	The composition and bonding structure of CN _x films and their influence on the mechanical properties. <i>Thin Solid Films</i> , 1997 , 308-309, 130-134	2.2	24
83	Electrochemical deposition of prussian blue films across interdigital array electrodes and their use in gas sensing. <i>Electroanalysis</i> , 1996 , 8, 195-198	3	23
82	Continuous atomic layer deposition: Explanation for anomalous growth rate effects. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A122	2.9	22
81	Atomic layer deposition of tin dioxide sensing film in microhotplate gas sensors. <i>Sensors and Actuators B: Chemical</i> , 2010 , 148, 227-232	8.5	22
80	Characterization of mixed-phase BN thin films deposited by plasma CVD. <i>Surface and Coatings Technology</i> , 1993 , 60, 502-505	4.4	21
79	Surface modification of polymers by plasma-assisted atomic layer deposition. <i>Surface and Coatings Technology</i> , 2011 , 205, S475-S479	4.4	20
78	Properties of mixed-phase BN films deposited by r.f. PACVD. <i>Thin Solid Films</i> , 1993 , 236, 96-102	2.2	20
77	Spatial atomic layer deposition: Performance of low temperature H ₂ O and O ₃ oxidant chemistry for flexible electronics encapsulation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 031603	2.9	19

76	Growth and characterisation of wide-bandgap, I-VII optoelectronic materials on silicon. <i>Journal of Materials Science: Materials in Electronics</i> , 2005 , 16, 415-419	2.1	19
75	Interaction of Plasma Deposited HMDSO-Based Coatings with Fibrinogen and Human Blood Plasma: The Correlation between Bulk Plasma, Surface Characteristics and Biomolecule Interaction. <i>Plasma Processes and Polymers</i> , 2010 , 7, 411-421	3.4	18
74	Impact on structural, optical and electrical properties of CuCl by incorporation of Zn for n-type doping. <i>Journal of Crystal Growth</i> , 2006 , 287, 139-144	1.6	17
73	Encapsulation of the heteroepitaxial growth of wide band gap CuCl on silicon substrates. <i>Journal of Crystal Growth</i> , 2006 , 287, 112-117	1.6	16
72	Investigation of the valence band states of reactively sputtered carbon nitride films. <i>Thin Solid Films</i> , 1999 , 355-356, 79-84	2.2	16
71	Catalytic Performance of Ag ₂ O and Ag Doped CeO ₂ Prepared by Atomic Layer Deposition for Diesel Soot Oxidation. <i>Coatings</i> , 2018 , 8, 237	2.9	16
70	Mechanical properties of atomic layer deposited Al ₂ O ₃ /ZnO nanolaminates. <i>Surface and Coatings Technology</i> , 2015 , 284, 198-205	4.4	15
69	Pre-treatment of substrates for improved adhesion of diamond-like carbon films on surgically implantable metals deposited by saddle field neutral beam source. <i>Surface and Coatings Technology</i> , 2003 , 174-175, 579-583	4.4	15
68	Measuring optical anisotropy in poly(3,4-ethylene dioxythiophene):poly(styrene sulfonate) films with added graphene. <i>Organic Electronics</i> , 2015 , 25, 317-323	3.5	14
67	Adhesion of carbon nitride thin films on tool steel. <i>Surface and Coatings Technology</i> , 1999 , 116-119, 46-53	4.4	14
66	Effect of substrate bias on the bonding structure of carbon nitride thin films. <i>Thin Solid Films</i> , 1999 , 355-356, 85-88	2.2	14
65	Magnetron sputtered carbon nitride films. <i>Surface and Coatings Technology</i> , 1994 , 68-69, 188-193	4.4	14
64	The structural and electron transport properties of CdS grown by molecular beam epitaxy. <i>Thin Solid Films</i> , 1979 , 58, 61-66	2.2	14
63	UV protective zinc oxide coating for biaxially oriented polypropylene packaging film by atomic layer deposition. <i>Thin Solid Films</i> , 2014 , 570, 33-37	2.2	13
62	Atomic layer deposition-A novel method for the ultrathin coating of minitablets. <i>International Journal of Pharmaceutics</i> , 2017 , 531, 47-58	6.5	13
61	On the ion flux and energy gain during pulsed DC operation of an opposed target magnetron. <i>Surface and Coatings Technology</i> , 2006 , 200, 5306-5317	4.4	13
60	Ambient air plasma pre-treatment of non-woven fabrics for deposition of antibacterial poly (l-lactide) nanoparticles. <i>Plasma Processes and Polymers</i> , 2017 , 14, 1600231	3.4	12
59	A Comparative Study of Characteristics of SiO _x CyHz, TiO _x and SiO-TiO Oxide-Based Biocompatible Coatings. <i>Plasma Processes and Polymers</i> , 2007 , 4, S369-S373	3.4	12

58	Evaluation of the chemical, electronic and optoelectronic properties of CuCl thin films and their fabrication on Si substrates. <i>Journal Physics D: Applied Physics</i> , 2007 , 40, 3461-3467	3	12
57	The effect of nitrogen partial pressure on the bonding in sputtered CN_x films: implications for formation of C_3N_4 . <i>Surface and Coatings Technology</i> , 2000 , 131, 488-492	4.4	12
56	Electrical properties of reactively sputtered carbon nitride films. <i>Surface and Coatings Technology</i> , 1999 , 116-119, 54-58	4.4	12
55	Planar self-aligned ion-implanted InP MOSFET. <i>Electronics Letters</i> , 1982 , 18, 534	1.1	12
54	Optical properties of DLC films deposited by the saddle field fast atom neutral beam source. <i>Journal of Materials Processing Technology</i> , 2005 , 169, 219-222	5.3	11
53	Influence of substrate contamination, web handling, and pretreatments on the barrier performance of aluminum oxide atomic layer-deposited BOPP film 2014 , 11, 775-784		10
52	Protecting BOPP film from UV degradation with an atomic layer deposited titanium oxide surface coating. <i>Applied Surface Science</i> , 2013 , 282, 506-511	6.7	10
51	The importance of the majority carrier polarity and p-n junction in titanium dioxide films to their photoactivity and photocatalytic properties. <i>Surface Science</i> , 2012 , 606, L22-L25	1.8	10
50	Adhesion of extrusion-coated polymer sealing layers to a fiber-based packaging material with an atomic layer deposited aluminum oxide surface coating. <i>Polymer Engineering and Science</i> , 2012 , 52, 1985-1990	2.3	10
49	Influence of oxygen depletion layer on the properties of tin oxide gas-sensing films fabricated by atomic layer deposition. <i>Applied Physics A: Materials Science and Processing</i> , 2009 , 95, 621-627	2.6	10
48	Nanoscratch testing of atomic layer deposition and magnetron sputtered TiO_2 and Al_2O_3 coatings on polymeric substrates. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A132	2.9	10
47	Pulsed dc operation of a Penning-type opposed target magnetron. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2005 , 23, 66-71	2.9	10
46	Hafnium oxide thin films as a barrier against copper diffusion in solar absorbers. <i>Solar Energy Materials and Solar Cells</i> , 2017 , 166, 140-146	6.4	9
45	Nucleation and initial growth of atomic layer deposited titanium oxide determined by spectroscopic ellipsometry and the effect of pretreatment by surface barrier discharge. <i>Applied Surface Science</i> , 2015 , 345, 216-222	6.7	9
44	Atomic layer deposition of CuCl nanoparticles. <i>Applied Physics Letters</i> , 2010 , 97, 241905	3.4	9
43	Penning type magnetron sputtering source and its use in the production of carbon nitride coatings. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1999 , 17, 62-69	2.9	9
42	Attachment of Poly(l-lactide) Nanoparticles to Plasma-Treated Non-Woven Polymer Fabrics Using Inkjet Printing. <i>Macromolecular Bioscience</i> , 2015 , 15, 1274-82	5.5	8
41	Nitrogen doping in atomic layer deposition grown titanium dioxide films by using ammonium hydroxide. <i>Thin Solid Films</i> , 2012 , 526, 212-217	2.2	8

40	DLC films deposited by a neutral beam source: adhesion to biological implant metals. <i>Surface and Coatings Technology</i> , 2003 , 169-170, 254-257	4.4	8
39	Surface chemistry and initial growth of Al ₂ O ₃ on plasma modified PTFE studied by ALD. <i>Surfaces and Interfaces</i> , 2017 , 6, 223-228	4.1	7
38	Effect of pulse frequency on the ion fluxes during pulsed dc magnetron sputtering. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2009 , 27, 282-286	2.9	7
37	The importance of the Pd to Sn ratio and of annealing cycles on the performance of Pd/Sn ohmiccontacts to n-GaAs. <i>Thin Solid Films</i> , 1997 , 292, 264-269	2.2	7
36	Plasma diagnostics in the growth of c-BN films. <i>Diamond and Related Materials</i> , 1994 , 3, 551-554	3.5	7
35	Atomic layer deposition of cerium oxide for potential use in diesel soot combustion. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 031506	2.9	7
34	(Invited) Molecular Layer Deposition. <i>ECS Transactions</i> , 2013 , 58, 263-275	1	6
33	Optical properties of CuCl films on silicon substrates. <i>Physica Status Solidi (B): Basic Research</i> , 2008 , 245, 2808-2814	1.3	6
32	Influence of target to substrate distance on the sputtered CuCl film properties. <i>Thin Solid Films</i> , 2008 , 516, 5531-5535	2.2	6
31	Magnetic fields in magnetron sputtering systems. <i>Surface and Coatings Technology</i> , 1993 , 57, 1-5	4.4	6
30	Structural and Optical Properties of Luminescent Copper(I) Chloride Thin Films Deposited by Sequentially Pulsed Chemical Vapour Deposition. <i>Coatings</i> , 2018 , 8, 369	2.9	6
29	ALD Applications and Industry 2013 , 215-242		5
28	Characterisation of n-type β -CuCl on Si for UV optoelectronic applications. <i>Journal of Materials Science: Materials in Electronics</i> , 2007 , 18, 57-60	2.1	5
27	Temperature dependent optical properties of UV emitting β -CuCl thin films. <i>Thin Solid Films</i> , 2008 , 516, 1439-1442	2.2	5
26	Factors influencing the performance of InP metal/insulator/semiconductor field effect transistors. <i>Thin Solid Films</i> , 1983 , 103, 61-70	2.2	5
25	Ion fluxes in medium frequency pulsed DC magnetron sputtering. <i>Surface and Coatings Technology</i> , 2010 , 204, 3131-3134	4.4	4
24	Thermal stability of the non-alloyed Pd/Sn and Pd/Ge Ohmic contacts to n-GaAs. <i>Thin Solid Films</i> , 1997 , 308-309, 607-610	2.2	4
23	Electrical studies on sputtered CuCl thin films. <i>Journal of Materials Science: Materials in Electronics</i> , 2008 , 19, 103-106	2.1	4

22	Magnetic field in two-dimensional magnetrons. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1995 , 13, 2151-2156	2.9	4
21	Effects of Au overlayers on the electrical and morphological characteristics of Pd/Sn ohmic contacts to n-GaAs. <i>Thin Solid Films</i> , 1996 , 290-291, 417-421	2.2	4
20	Substrate effects on performance of InP MOSFETs. <i>Electronics Letters</i> , 1982 , 18, 415	1.1	4
19	Controlled fabrication and electrowetting properties of silicon nanostructures. <i>Journal of Adhesion Science and Technology</i> , 2017 , 31, 31-40	2	3
18	Atomic layer deposition of nanocrystallite arrays of copper(I) chloride for optoelectronic structures. <i>Journal of Materials Science: Materials in Electronics</i> , 2017 , 28, 11695-11701	2.1	3
17	Properties of Pd/Sn Ohmic contacts on n-GaAs. <i>Journal of Materials Processing Technology</i> , 1998 , 77, 42-49	5.3	3
16	Morphological, optical and electrical properties of [CuCl deposited by vacuum evaporation. <i>Journal of Materials Science: Materials in Electronics</i> , 2008 , 19, 99-101	2.1	3
15	Comparison of the operating characteristics of an opposed target magnetron using ferromagnetic and non-ferromagnetic targets. <i>Surface and Coatings Technology</i> , 2005 , 200, 644-648	4.4	3
14	Comparison of Pd/Sn and Pd/Sn/Au Thin-Film Systems for Device Metallization. <i>Materials Research Society Symposia Proceedings</i> , 1996 , 427, 583		3
13	Enhancement of Atmospheric Plasma Decomposition of Toluene Using Porous Dielectric Conformally Coated with Titanium Dioxide by Atomic Layer Deposition. <i>Science of Advanced Materials</i> , 2014 , 6, 2098-2105	2.3	3
12	Fundamentals of Atomic Layer Deposition 2013 , 1-31		2
11	The correlation of channel mobility with interface state measurements on InP MOSFET structures. <i>Solid-State Electronics</i> , 1984 , 27, 305-309	1.7	2
10	Junction characteristics of Al-Al ₂ O ₃ -CdS diodes fabricated by molecular beam epitaxy. <i>Applied Physics Letters</i> , 1979 , 34, 413-415	3.4	2
9	Stress behaviour of reactively sputtered nitrogenated carbon films. <i>Surface and Coatings Technology</i> , 1998 , 98, 985-990	4.4	1
8	A three-step algorithm for solving 2D inverse magnetostatic problems for magnetron design applications. <i>Inverse Problems in Science and Engineering</i> , 2005 , 13, 279-297	1.3	1
7	The use of wide-bandgap CuCl on silicon for ultra-violet photonics 2005 ,		1
6	Optical investigations on sputtered CuCl thin films. <i>Materials Research Society Symposia Proceedings</i> , 2005 , 891, 1		1
5	Plasma deposition of hard carbon films as wear protective coatings. <i>Journal of Materials Processing Technology</i> , 1991 , 26, 117-132	5.3	1

- 4 Ellipsometry, reflectance, and photoluminescence of nanocrystalline CuCl thin films on silicon. *Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics*, **2019**, 37, 051206 1.3
- 3 Oxide films **2013**, 67-159
- 2 Organic and Hybrid Materials **2013**, 207-213
- 1 Magnetic Field in a Commercial Sputter Magnetron. *Key Engineering Materials*, **1996**, 118-119, 287-294 0.4